

	L #	Hits	Search Text	DBs	Time Stamp
1	L2	622647	(flip adj chip or BGA or (ball adj grid) or IC or device or package or die or dice or dies) near8 (board or substrate or wafer or PCB or (print adj circuit adj board) or MCM or multi-chip or (multi adj chip) or interposer or leadframe or (lead adj frame))	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
2	L3	331368 7	(diisocyanate adj monomers) or (diisocynate adj end-capped adj compliant adj oligomer) or (ptoluenesulfonyl adj semicarbazide) or (hydroxyl adj end-capped adj oligomer) or (carboxylic adj acid adj polymer) or water or "H.sub.20" or (polymer\$6 near2 foam\$6)	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
3	L4	60741	((diisocyanate adj monomers) or (diisocynate adj end-capped adj compliant adj oligomer) or (ptoluenesulfonyl adj semicarbazide) or (hydroxyl adj end-capped adj oligomer) or (carboxylic adj acid adj polymer) or water or "H.sub.20" or (polymer\$6 near2 foam\$6)) near4 (filling or filler or infill or insulat\$4)	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24

	L #	Hits	Search Text	DBs	Time Stamp
4	L5	1840	(((diisocyanate adj monomers) or (diisocynate adj end-capped adj compliant adj oligomer) or (ptoluenesulfonyl adj semicarbazide) or (hydroxyl adj end-capped adj oligomer) or (carboxylic adj acid adj polymer) or water or "H.sub.20" or (polymer\$6 near2 foam\$6)) near4 (filling or filler or infill or insulat\$4)) and ((flip adj chip or BGA or (ball adj grid) or IC or device or package or die or dice or dies) near8 (board or substrate or wafer or PCB or (print adj circuit adj board) or MCM or multi-chip or (multi adj chip) or interposer or leadframe or (lead adj frame)))	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
5	L6	331055 4	(diisocyanate adj monomers) or (diisocynate adj end-capped adj compliant adj oligomer) or (ptoluenesulfonyl adj semicarbazide) or (hydroxyl adj end-capped adj oligomer) or (carboxylic adj acid adj polymer) or water or (polymer\$6 near2 foam\$6)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24

	L #	Hits	Search Text	DBs	Time Stamp
6	L7	113279	((diisocyanate adj monomers) or (diisocynate adj end-capped adj compliant adj oligomer) or (ptoluenesulfonyl adj semicarbazide) or (hydroxyl adj end-capped adj oligomer) or (carboxylic adj acid adj polymer) or water or (polymer\$6 near2 foam\$6)) near4 (filling or filler or infill or insulat\$4 or support\$4)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
7	L8	829700	interconnect\$6 or inter-connect\$6	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
8	L9	251535 9	reaction or react\$6 or polymerization	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
9	L10	215258 0	substrate or wafer	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24

	L #	Hits	Search Text	DBs	Time Stamp
10	L11	29699	polymer\$4 near2 (foam\$6 or bubbles or spray\$6)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
11	L12	53452	(expose\$4 or top or surface) near4 (interconnect\$6 or interconnect\$6)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
12	L13	23417	polymer\$4 near2 foam\$6	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
13	L14	537	(polymer\$4 near2 foam\$6) near4 (substrates or wafers)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24

	L #	Hits	Search Text	DBs	Time Stamp
14	L15	605	(polymer\$4 near2 foam\$6) same interconnect\$6	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
15	L16	544	(438/782).CCLS.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
16	L17	2503	((438/762).CCLS.) or ((438/765).CCLS.) or ((438/780).CCLS.) or ((438/782).CCLS.)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
17	L18	1611	(438/780).CCLS.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24

	L #	Hits	Search Text	DBs	Time Stamp
18	L34	37708	substrates near8 interconnect\$6	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
19	L35	26656	(second! adj (substrate or wafer)) same (first adj (substrate or wafer))	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
20	L36	1001	((second! adj (substrate or wafer)) same (first adj (substrate or wafer))) same interconnect\$6	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
21	L37	929	((second! adj (substrate or wafer)) same (first adj (substrate or wafer))) same interconnect\$6) and ((@ad<"20030620") or (@rlad<"20030620"))	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24

	L #	Hits	Search Text	DBs	Time Stamp
22	L21	6	((expose\$4 or top or surface) near4 (interconnect\$6 or interconnect\$6)) same (reaction or react\$6 or polymerization) same (substrate or wafer)) and (polymer\$4 near2 (foam\$6 or bubbles or spray\$6))	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	2005/04/08 16:24
23	L25	20	((polymer\$4 near2 foam\$6) near4 (substrates or wafers)) same interconnect\$6	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	2005/04/08 16:24
24	L26	24	((polymer\$4 near2 foam\$6) near4 (substrates or wafers)) same (inject\$6 or spray\$6 or diffus\$6 or immers\$6)	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	2005/04/08 16:24
25	L28	9	((438/762).CCLS.) or ((438/765).CCLS.) or ((438/780).CCLS.) or ((438/782).CCLS.)) and (polymer\$4 near2 foam\$6)	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	2005/04/08 16:24

	L #	Hits	Search Text	DBs	Time Stamp
26	L32	77	(((polymer\$4 near2 foam\$6) near4 (substrates or wafers)) and interconnect\$6) and ((@ad<"20030620") or (@rlad<"20030620"))	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	2005/04/08 16:24
27	L1	175	(((diisocyanate adj monomers) or (diisocynate adj end-capped adj compliant adj oligomer) or (ptoluenesulfonyl adj semicarbazide) or (hydroxyl adj end-capped adj oligomer) or (carboxylic adj acid adj polymer) or water or "H.sub.20" or (polymer\$6 near2 foam\$6)) near4 (filling or filler or infill or insulat\$4)) same ((flip adj chip or BGA or (ball adj grid) or IC or device or package or die or dice or dies) near8 (board or substrate or wafer or PCB or (print adj circuit adj board) or MCM or multi-chip or (multi adj chip) or interposer or leadframe or (lead adj frame)))	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	2005/04/08 16:24

	L #	Hits	Search Text	DBs	Time Stamp
28	L19	175	(((diisocyanate adj monomers) or (diisocynate adj end-capped adj compliant adj oligomer) or (ptoluenesulfonyl adj semicarbazide) or (hydroxyl adj end-capped adj oligomer) or (carboxylic adj acid adj polymer) or water or "H.sub.2O" or (polymer\$6 near2 foam\$6)) near4 (filling or filler or infill or insulat\$4)) same ((flip adj chip or BGA or (ball adj grid) or IC or device or package or die or dice or dies) near8 (board or substrate or wafer or PCB or (print adj circuit adj board) or MCM or multi-chip or (multi adj chip) or interposer or leadframe or (lead adj frame)))	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
29	L30	171	(438/765).CCLS.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
30	L27	255	((polymer\$4 near2 foam\$6) same interconnect\$6) and (substrate or wafer)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24

	L #	Hits	Search Text	DBs	Time Stamp
31	L33	249	(((polymer\$4 near2 foam\$6) same interconnect\$6) and (substrate or wafer)) and ((@ad<"20030620") or (@rlad<"20030620"))	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
32	L20	320	(((diisocyanate adj monomers) or (diisocynate adj end-capped adj compliant adj oligomer) or (ptoluenesulfonyl adj semicarbazide) or (hydroxyl adj end-capped adj oligomer) or (carboxylic adj acid adj polymer) or water or (polymer\$6 near2 foam\$6)) near4 (filling or filler or infill or insulat\$4 or support\$4)) same ((flip adj chip or BGA or (ball adj grid) or IC or device or package or die or dice or dies) near8 (board or substrate or wafer or PCB or (print adj circuit adj board) or MCM or multi- chip or (multi adj chip) or interposer or leadframe or (lead adj frame)))	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24

	L #	Hits	Search Text	DBs	Time Stamp
33	L23	367	((expose\$4 or top or surface) near4 (interconnect\$6 or interconnect\$6)) same (reaction or react\$6 or polymerization) same (substrate or wafer)) and ((flip adj chip or BGA or (ball adj grid) or IC or device or package or die or dice or dies) near8 (board or substrate or wafer or PCB or (print adj circuit adj board) or MCM or multi-chip or (multi adj chip) or interposer or leadframe or (lead adj frame)))	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
34	L24	334	(polymer\$4 near2 (foam\$6 or bubbles or spray\$6)) and ((expose\$4 or top or surface) near4 (interconnect\$6 or interconnect\$6))	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24
35	L29	391	(438/762).CCLS.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:24

	L #	Hits	Search Text	DBs	Time Stamp
36	L38	337	(((((second! adj (substrate or wafer)) same (first adj (substrate or wafer))) same interconnect\$6) and ((@ad<"20030620") or (@rlad<"20030620")) and polymer\$6	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	2005/04/08 16:24
37	L22	584	((expose\$4 or top or surface) near4 (interconnect\$6 or interconnect\$6)) same (reaction or react\$6 or polymerization) same (substrate or wafer)	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	2005/04/08 16:24
38	L31	80	((polymer\$4 near2 foam\$6) near4 (substrates or wafers)) and interconnect\$6	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	2005/04/08 16:46
39	L39	588	(257/618).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	2005/04/08 16:46

	L #	Hits	Search Text	DBs	Time Stamp
40	L41	1699	((438/107) or (438/109)).CCLS.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:47
41	L42	459	39 and (@ad<"20030620") or (@rlad<"20030630"))	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:49
42	L44	130	42 and interconnect\$6	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:49

	L #	Hits	Search Text	DBs	Time Stamp
43	L45	23	44 and (second near (substrate or wafer))	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 16:50
44	L46	604	(257/620).CCLS.	US- PGPUB; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TD B	2005/04/08 17:31

DOCUMENT-IDENTIFIER: US 20030203663 A1

TITLE: Electrical interconnect using locally
conductive adhesive

----- KWIC -----

Pre-Grant Publication Document Identifier - DID
(1):

US 20030203668 A1

Summary of Invention Paragraph - BSTX (15):

[0013] In yet another preferred embodiment, the invention is an electrical interconnect comprising: (a) a first substrate having a surface and at least one first electrical contact projecting from the first substrate surface; (b) a second substrate having a surface and at least one second electrical contact projecting from the second substrate surface and aligned with the first electrical contact, such that the first substrate surface is substantially parallel to the second substrate surface; and, (c) an adhesive interposed between and in contact with the first electrical contact and the second electrical contact, the adhesive comprising an electrically non-conductive resin and particles, the particles comprising a core of at least one electrically conductive reactive material and a breakable coating of at least one electrically non-conductive material, the core comprising: (1) at least one first subparticle comprising a reactive resin, having conductive material therein, encapsulated inside a rupturable membrane; and, (2) at least one second subparticle comprising a catalyst encapsulated inside a rupturable membrane, wherein the first electrical contact is positioned close enough to the second electrical contact to break the breakable coating of the particles in the interposed adhesive such that the first subparticle membrane and the

second subparticle membrane are ruptured, whereby the reactive resin and the catalyst react to form a conductive adhesive between the first electrical contact and the second electrical contact provided that the coating of the particles interposed between the first substrate surface and the second substrate surface, but not interposed between the first electrical contact and the second electrical contact, is not broken. This embodiment includes semiconductor dies or chips and semiconductor packages comprising such an interconnect.

Summary of Invention Paragraph - BSTX (17):

[0015] In another preferred embodiment, the invention is an electrical interconnect comprising: (a) a first substrate having a surface and at least one first electrical contact projecting from the first substrate surface; (b) a second substrate having a surface and at least one second electrical contact projecting from the second substrate surface and aligned with the first electrical contact, such that the first substrate surface is substantially parallel to the second substrate surface; and, (c) an adhesive interposed between and in contact with the first electrical contact and the second electrical contact, the adhesive comprising: (1) an electrically non-conductive resin; (2) multiple first particles, each first particle comprising a core comprising at least one reactive resin, having an electrically conductive material therein, and a breakable coating of at least one electrically non-conductive material; and (3) multiple second particles, each second particle comprising a core comprising a catalyst and a breakable coating of at least one electrically non-conductive material, wherein the first electrical contact is positioned close enough to the second electrical contact to break the breakable coatings of the first particles and the second

particles in the
interposed adhesive, whereby the reactive resin and the catalyst
react to form
a conductive adhesive between the first electrical contact and the
second
electrical contact, contact provided that the coating of the
particles
interposed between the first substrate surface and the second
substrate
surface, but not interposed between the first electrical contact and
the second
electrical contact, is not broken. This embodiment includes
semiconductor dies
or chips and semiconductor packages comprising such an interconnect.

Claims Text - CLTX (40):

39. An electrical interconnect comprising: (a) a first substrate
having a
surface and at least one first electrical contact projecting from the
first
substrate surface; (b) a second substrate having a surface and at
least one
second electrical contact projecting from the second substrate
surface and
aligned with the first electrical contact, such that the first
substrate
surface is substantially parallel to the second substrate surface;
and, (c) a
first adhesive interposed between and in contact with the first
electrical
contact and the second electrical contact, the first adhesive
comprising an
electrically nonconductive resin and particles, the particles
comprising a core
and a breakable coating of at least one electrically non-conductive
material,
the core comprising: (1) at least one first subparticle comprising a
reactive
resin, having conductive material therein, encapsulated inside a
rupturable
membrane; and, (2) at least one second subparticle comprising a
catalyst
encapsulated inside a rupturable membrane, wherein the first
electrical contact
is positioned close enough to the second electrical contact to break
the
breakable coating of the particles in the interposed first adhesive
such that
the first subparticle membrane and the second subparticle membrane
are

ruptured, whereby the reactive resin and the catalyst react to form a conductive second adhesive between the first electrical contact and the second electrical contact provided that the coating of the particles interposed between the first substrate surface and the second substrate surface, but not interposed between the first electrical contact and the second electrical contact, is not broken.

Claims Text - CLTX (46):

45. A semiconductor die or chip comprising an electrical interconnect, wherein the electrical interconnect comprises: (a) a first substrate having a surface and at least one first electrical contact projecting from the first substrate surface; (b) a second substrate having a surface and at least one second electrical contact projecting from the second substrate surface and aligned with the first electrical contact, such that the first substrate surface is substantially parallel to the second substrate surface; and, (c) a first adhesive interposed between and in contact with the first electrical contact and the second electrical contact, the first adhesive comprising an electrically nonconductive resin and particles, the particles comprising a core and a breakable coating of at least one electrically non-conductive material, the core comprising: (1) at least one first subparticle comprising a reactive resin, having conductive material therein, encapsulated inside a rupturable membrane; and, (2) at least one second subparticle comprising a catalyst encapsulated inside a rupturable membrane, wherein the first electrical contact is positioned close enough to the second electrical contact to break the breakable coating of the particles in the interposed first adhesive such that the first subparticle membrane and the second subparticle membrane are ruptured, whereby the reactive resin and the catalyst react to form a conductive second adhesive between the first electrical contact and

the second
electrical contact provided that the coating of the particles
interposed
between the first substrate surface and the second substrate surface,
but not
interposed between the first electrical contact and the second
electrical
contact, is not broken.

Claims Text - CLTX (52):

51. A semiconductor package comprising an electrical
interconnect, wherein
the electrical interconnect comprises: (a) a first substrate having a
surface
and at least one first electrical contact projecting from the first
substrate
surface; (b) a second substrate having a surface and at least one
second
electrical contact projecting from the second substrate surface and
aligned
with the first electrical contact, such that the first substrate
surface is
substantially parallel to the second substrate surface; and, (c) a
first
adhesive interposed between and in contact with the first electrical
contact
and the second electrical contact, the first adhesive comprising an
electrically nonconductive resin and particles, the particles
comprising a core
and a breakable coating of at least one electrically non-conductive
material,
the core comprising: (1) at least one first subparticle comprising a
reactive
resin, having conductive material therein, encapsulated inside a
rupturable
membrane; and, (2) at least one second subparticle comprising a
catalyst
encapsulated inside a rupturable membrane, wherein the first
electrical contact
is positioned close enough to the second electrical contact to break
the
breakable coating of the particles in the interposed first adhesive
such that
the first subparticle membrane and the second subparticle membrane
are
ruptured, whereby the reactive resin and the catalyst react to form a
conductive second adhesive between the first electrical contact and
the second
electrical contact provided that the coating of the particles
interposed

between the first substrate surface and the second substrate surface, but not interposed between the first electrical contact and the second electrical contact, is not broken.

Claims Text - CLTX (64):

63. An electrical interconnect comprising: (a) a first substrate having a surface and at least one first electrical contact projecting from the first substrate surface; (b) a second substrate having a surface and at least one second electrical contact projecting from the second substrate surface and aligned with the first electrical contact, such that the first substrate surface is substantially parallel to the second substrate surface; and, (c) a first adhesive interposed between and in contact with the first electrical contact and the second electrical contact, the second adhesive comprising: (1) an electrically nonconductive resin; (2) multiple first particles, each first particle comprising a core comprising at least one reactive resin, having an electrically conductive material therein, and a breakable coating of at least one electrically non-conductive material; and (3) multiple second particles, each second particle comprising a core comprising a catalyst and a breakable coating of at least one electrically non-conductive material, wherein the first electrical contact is positioned close enough to the second electrical contact to break the breakable coatings of the first particles and the second particles in the interposed first adhesive, whereby the reactive resin and the catalyst react to form a conductive second adhesive between the first electrical contact and the second electrical contact, contact provided that the coating of the particles interposed between the first substrate surface and the second substrate surface, but not interposed between the first electrical contact and the second electrical contact, is not broken.

Claims Text - CLTX (70):

69. A semiconductor die or chip comprising an electrical interconnect, wherein the electrical interconnect comprises: (a) a first substrate having a surface and at least one first electrical contact projecting from the first substrate surface; (b) a second substrate having a surface and at least one second electrical contact projecting from the second substrate surface and aligned with the first electrical contact, such that the first substrate surface is substantially parallel to the second substrate surface; and, (c) a first adhesive interposed between and in contact with the first electrical contact and the second electrical contact, the second adhesive comprising: (1) an electrically nonconductive resin; (2) multiple first particles, each first particle comprising a core comprising at least one reactive resin, having an electrically conductive material therein, and a breakable coating of at least one electrically non-conductive material; and (3) multiple second particles, each second particle comprising a core comprising a catalyst and a breakable coating of at least one electrically non-conductive material, wherein the first electrical contact is positioned close enough to the second electrical contact to break the breakable coatings of the first particles and the second particles in the interposed first adhesive, whereby the reactive resin and the catalyst react to form a conductive second adhesive between the first electrical contact and the second electrical contact, contact provided that the coating of the particles interposed between the first substrate surface and the second substrate surface, but not interposed between the first electrical contact and the second electrical contact, is not broken.

Claims Text - CLTX (76):

75. A semiconductor package comprising an electrical

interconnect, wherein
the electrical interconnect comprises: (a) a first substrate having a surface
and at least one first electrical contact projecting from the first substrate
surface; (b) a second substrate having a surface and at least one
second
electrical contact projecting from the second substrate surface and
aligned
with the first electrical contact, such that the first substrate
surface is
substantially parallel to the second substrate surface; and, (c) a
first
adhesive interposed between and in contact with the first electrical
contact
and the second electrical contact, the first adhesive comprising: (1)
an
electrically nonconductive resin; (2) multiple first particles, each
first
particle comprising a core comprising at least one reactive resin,
having an
electrically conductive material therein, and a breakable coating of
at least
one electrically non-conductive material; and (3) multiple second
particles,
each second particle comprising a core comprising a catalyst and a
breakable
coating of at least one electrically non-conductive material, wherein
the first
electrical contact is positioned close enough to the second
electrical contact
to break the breakable coatings of the first particles and the second
particles
in the interposed first adhesive, whereby the reactive resin and the
catalyst
react to form a conductive second adhesive between the first
electrical contact
and the second electrical contact, contact provided that the coating
of the
particles interposed between the first substrate surface and the
second
substrate surface, but not interposed between the first electrical
contact and
the second electrical contact, is not broken.